

	Hits	Search Text	DBs
1	7332	(RIE (reactive adj ion adj etch\$3)) and optic\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
2	1487	((RIE (reactive adj ion adj etch\$3)) and optic\$4) and (CF4 "CF.sub.4")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
3	40	((RIE (reactive adj ion adj etch\$3)) and optic\$4) and plume	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
4	328	plasma near plume	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
5	4	(plasma near plume) and (RIE (reactive adj ion adj etch\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
6	4	(((((plasma near plume) and (RIE (reactive adj ion adj etch\$3))) (plasma adj jet and (RIE (reactive adj ion adj etch\$3))) (plasma adj torch and (RIE (reactive adj ion adj etch\$3)))) and (CF4 "CF.sub.4") (((plasma near plume) and (RIE (reactive adj ion adj etch\$3))) (plasma adj jet and (RIE (reactive adj ion adj etch\$3))) (plasma adj torch and (RIE (reactive adj ion adj etch\$3)))) and (sF6 "sF.sub.6") (((plasma near plume) and (RIE (reactive adj ion adj etch\$3))) (plasma adj jet and (RIE (reactive adj ion adj etch\$3))) (plasma adj torch and (RIE (reactive adj ion adj etch\$3)))) and (c2f6 "c.sub.2 F.sub.6")) and (((plasma near plume) and (RIE (reactive adj ion adj etch\$3))) (plasma adj jet and (RIE (reactive adj ion adj etch\$3))) (plasma adj torch and (RIE (reactive adj ion adj etch\$3)))) and optic\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
7	17	(((((plasma near plume) and (RIE (reactive adj ion adj etch\$3))) (plasma adj jet and (RIE (reactive adj ion adj etch\$3))) (plasma adj torch and (RIE (reactive adj ion adj etch\$3)))) and (CF4 "CF.sub.4") (((plasma near plume) and (RIE (reactive adj ion adj etch\$3))) (plasma adj jet and (RIE (reactive adj ion adj etch\$3))) (plasma adj torch and (RIE (reactive adj ion adj etch\$3)))) and (sF6 "sF.sub.6") (((plasma near plume) and (RIE (reactive adj ion adj etch\$3))) (plasma adj jet and (RIE (reactive adj ion adj etch\$3))) (plasma adj torch and (RIE (reactive adj ion adj etch\$3)))) and (c2f6 "c.sub.2 F.sub.6"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
8	43	((plasma near plume) and (RIE (reactive adj ion adj etch\$3))) (plasma adj jet and (RIE (reactive adj ion adj etch\$3))) (plasma adj torch and (RIE (reactive adj ion adj etch\$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
9	6	(((((plasma near plume) and (RIE (reactive adj ion adj etch\$3))) (plasma adj jet and (RIE (reactive adj ion adj etch\$3))) (plasma adj torch and (RIE (reactive adj ion adj etch\$3)))) and (c2f6 "c.sub.2 F.sub.6")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

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10	9	((((plasma near plume) and (RIE (reactive adj ion adj etch\$3))) (plasma adj jet and (RIE (reactive adj ion adj etch\$3))) (plasma adj torch and (RIE (reactive adj ion adj etch\$3)))) and (CF4 "CF.sub.4")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
11	13	((((plasma near plume) and (RIE (reactive adj ion adj etch\$3))) (plasma adj jet and (RIE (reactive adj ion adj etch\$3))) (plasma adj torch and (RIE (reactive adj ion adj etch\$3)))) and (sF6 "sF.sub.6")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
12	21	((((plasma near plume) and (RIE (reactive adj ion adj etch\$3))) (plasma adj jet and (RIE (reactive adj ion adj etch\$3))) (plasma adj torch and (RIE (reactive adj ion adj etch\$3)))) and optic\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
13	13	plasma adj torch and (RIE (reactive adj ion adj etch\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
14	29	plasma adj jet and (RIE (reactive adj ion adj etch\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
15	0	PCT/US97/18979	EPO; DERWENT
16	0	US9718979	EPO; DERWENT
17	2	"9718979"	EPO; DERWENT
18	25	siniaguine.in.	EPO; DERWENT
19	649	(plasma near (plume jet torch)) and (CF4 SF6 C2F6 "CF.sub.4" "SF.sub.6" "C.sub.2 F.sub.6" etch\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
20	54	((plasma near (plume jet torch)) and (CF4 SF6 C2F6 "CF.sub.4" "SF.sub.6" "C.sub.2 F.sub.6" etch\$3)) and (CF4 SF6 C2F6 "CF.sub.4" "SF.sub.6" "C.sub.2 F.sub.6") and etch\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
21	41	((((plasma near (plume jet torch)) and (CF4 SF6 C2F6 "CF.sub.4" "SF.sub.6" "C.sub.2 F.sub.6" etch\$3)) and (CF4 SF6 C2F6 "CF.sub.4" "SF.sub.6" "C.sub.2 F.sub.6") and etch\$3)) and (CF4 SF6 C2F6 "CF.sub.4" "SF.sub.6" "C.sub.2 F.sub.6") same etch\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
22	1	((plasma near (plume jet torch)) and (CF4 SF6 C2F6 "CF.sub.4" "SF.sub.6" "C.sub.2 F.sub.6" etch\$3)) and shaping adj surface	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
23	26	((((plasma near (plume jet torch)) and (CF4 SF6 C2F6 "CF.sub.4" "SF.sub.6" "C.sub.2 F.sub.6" etch\$3)) and (CF4 SF6 C2F6 "CF.sub.4" "SF.sub.6" "C.sub.2 F.sub.6") and etch\$3)) and (CF4 SF6 C2F6 "CF.sub.4" "SF.sub.6" "C.sub.2 F.sub.6") same etch\$3) and (ar argon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
24	4	((plasma near (plume jet torch)) and (CF4 SF6 C2F6 "CF.sub.4" "SF.sub.6" "C.sub.2 F.sub.6" etch\$3)) and aspheric\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB

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25	0	((plasma near (plume jet torch)) and (CF4 SF6 C2F6 "CF.sub.4" "SF.sub.6" "C.sub.2 F.sub.6" etch\$3)) and silica adj glass adj optic	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
26	28	((plasma near (plume jet torch)) and (CF4 SF6 C2F6 "CF.sub.4" "SF.sub.6" "C.sub.2 F.sub.6" etch\$3)) and silica adj glass	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
27	4747	Rapp (reactive adj atom adj plasma)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
28	0	Rapp and (reactive adj atom adj plasma)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
29	0	reactive adj atom adj plasma	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
30	89	plasma near polishing	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
31	27	plasma adj polishing	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
32	62	(plasma near polishing) not (plasma adj polishing)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
33	16	((plasma near polishing) not (plasma adj polishing)) and damage	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB
34	46	((plasma near polishing) not (plasma adj polishing)) not (((plasma near polishing) not (plasma adj polishing)) and damage)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB